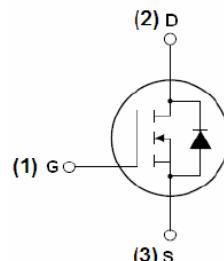


Trench N-Channel PowerMOSFET Wafer Datasheet

FEATURES

- 100V、80A*, N-channel
- $R_{DS(on)}=8.5\text{m}\Omega(\text{MAX})$
- Ultra low Q_{gd}
- Fast switching



Electrical Characteristics($T_J=25^\circ\text{C}$)

Parameter	Description	Min.	Typ.	Max.	Unit	Test Condition
$V_{(\text{BR})\text{DSS}}$	Drain-Source Breakdown Voltage	100			V	$V_{GS}=0\text{V}, I_D=250\mu\text{A}$
$R_{DS(\text{on})}$	Static Drain-Source On-Resistance		7.2	8.5	$\text{m}\Omega$	$V_{GS}=10\text{V}, I_D=39\text{A}$
			9.5	12	$\text{m}\Omega$	$V_{GS}=4.5\text{V}, I_D=39\text{A}$
$V_{GS(\text{th})}$	Gate Threshold Voltage	1.0		2.2	V	$V_{DS}=V_{GS}, I_D=250\mu\text{A}$
I_{DSS}	Drain-to-Source Leakage Current			1	μA	$V_{DS}=100\text{V}, V_{GS}=0\text{V}, T_J=25^\circ\text{C}$
I_{GSS}	Gate-Body Leakage Current			± 100	nA	$V_{GS}=\pm 20\text{V}$
V_{SD}	Body Diode Voltage			1.5	V	$V_{GS}=0\text{V}, I_{SD}=80\text{A}$
T_J, T_{stg}	Operating and Storage Temperature Range	-55~+150			°C	

Mechanical Date

Die Size	3158×2600	μm^2	
Gate Pad Size	254×414		
Source Pad Size	No Passivation		
Scribe Line Size	80		
Wafer Diameter	200		
Wafer Thickness	200		
Passivation Frontside	No Passivation		
Source Metallization	AlCu , 4.0		
Drain Metallization	Ti-Ni-Ag 1K-2K-10K		
Reject Ink Dot Size	0.51		
Recommended Storage Environment	Store in original container, in desiccated nitrogen, with no contamination		

* Electrical characteristics are reported for the reference packaged part (TO-220/263) and cannot be guaranteed in die sales form.

Variations in customer packaging materials, dimensions and processes may affect parametric performance.